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PATENT

Docket No. H 3475 PCT/US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Huber Schenkel

International Application No. PCT/EP99/07143
International Filing Date: September 25, 1999

Serial No. To be assigned
Filed: To be assigned

Examiner: To be assigned
Art Unit: To be assigned

Title: IMPACT-RESISTANT EPOXIDE RESIN COMPOSITIONS

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PRELIMINARY AMENDMENT

Box PCT
Assistant Commissioner for Patents
Washington, DC 20231

Attn: DO/EO/US

Sir:

Prior to examining this application, please amend the application as follows:

In the Specification (Using the English Translation):

On page 1 of the English translation, on a separate line between the title and line 1, please insert the following:

-- CROSS REFERENCE TO RELATED APPLICATIONS

This application is a national stage application under 35 U.S.C. § 371 of international application PCT/EP99/07143 filed on September 25, 1999, the international

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AI application not being published in English. This application also claims priority under
35 U.S.C. §119 to DE 198 45 607.7 filed on October 6, 1998.

FIELD OF THE INVENTION --.

On page 1, between lines 9 and 10, please insert the header
-- BACKGROUND OF THE INVENTION --.

On page 5, between lines 22 and 23, please insert the header:
-- DETAILED DESCRIPTION OF THE INVENTION --.

On page 19, line 1, please delete the heading "~~CLAIMS~~" and insert therefor:
-- What is claimed is: --

On a separate page, after page 21, please insert the enclosed Abstract of the Disclosure.

In the Claims

Please cancel claims 1 to 14, without prejudice.

Please add the following new claims:

15. (New) A composition comprising
- (a) at least one copolymer having at least one glass transition temperature of -30°C or lower and one or more epoxy-reactive groups;
 - (b) a product bearing one or more terminal phenolic or amino groups wherein the product is formed by a reaction comprising (i) reacting a stoichiometric excess of at least one carboxylic anhydride or carboxylic dianhydride with at least one diamine or polyamine; and (ii) reacting one or more of the excess carboxylic anhydride groups or carboxylic acid groups derived from the excess anhydride groups with a stoichiometric excess of at least one polyphenol or aminophenol; and
 - (c) at least one first epoxy resin.